

# 微機電系統簡介

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<http://mdl.pme.nthu.edu.tw>



# 前言



## About MEMS



1 mm



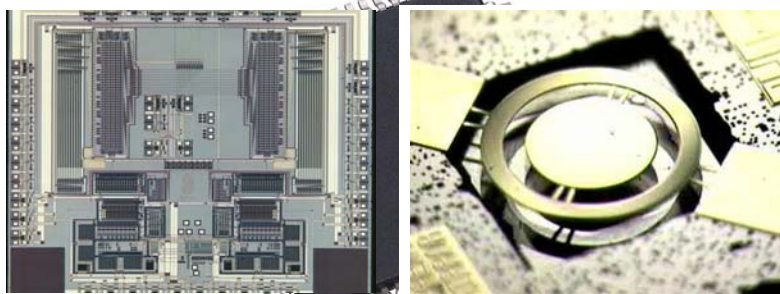
請大動機系微機電系統實驗室



## What's MEMS

IC

MEMS



<http://www.aztex.biz/general-computer/integrated-circuit-work/>  
Texas Instruments Inc.

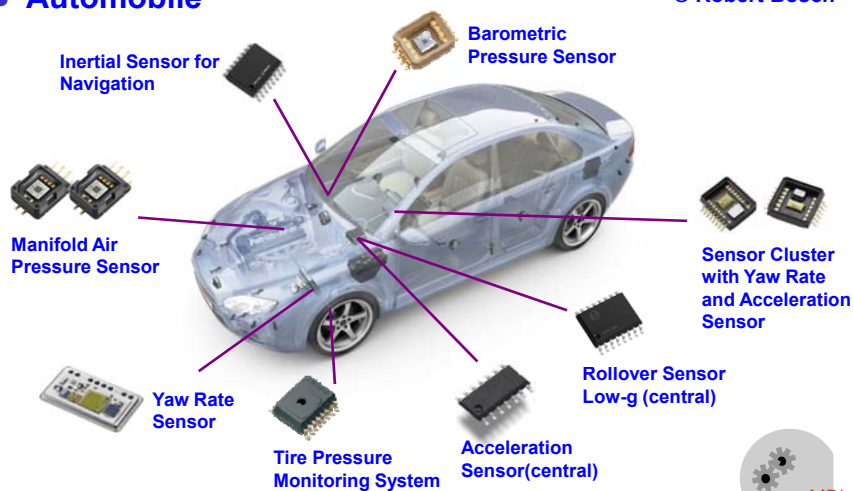
MDL



## Where's MEMS

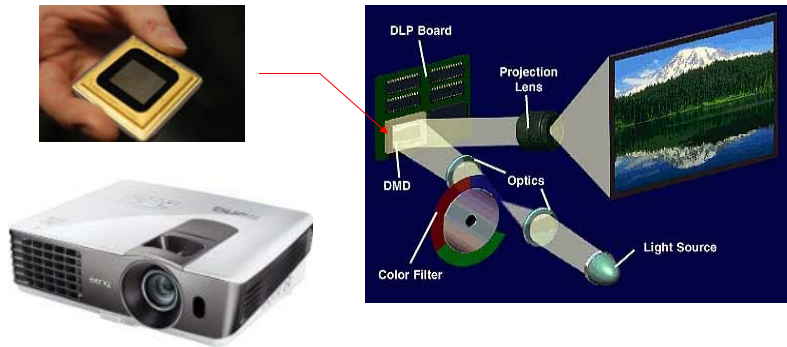
### • Automobile

© Robert Bosch



## Where's MEMS

- Before 2000 – inkjet printer, projector



Texas Instruments Inc.



## Where's MEMS

- 2006~2013 – consumer electronics



Wii



Smart phone

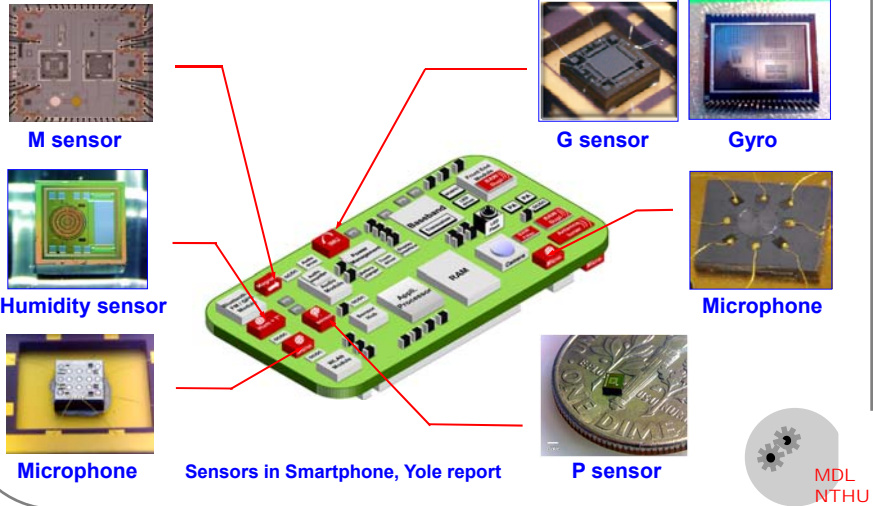


Wearable



## Where's MEMS

- MEMS Devices in volume in 2013 (from Yole)



## Where's MEMS

- Internet of Things (IoT)



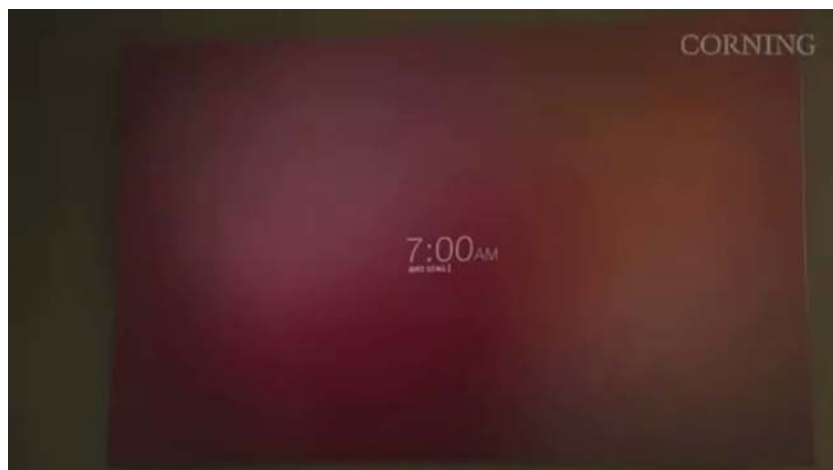
## Corning - A Day Made of Glass



<http://www.corning.com/index.aspx>



## Corning - A Day Made of Glass



<http://www.corning.com/index.aspx>



## Parrot - Drone



Lightweight yet robust design.

<http://www.parrot.com/>



## Parrot - Drone



<http://www.parrot.com/>



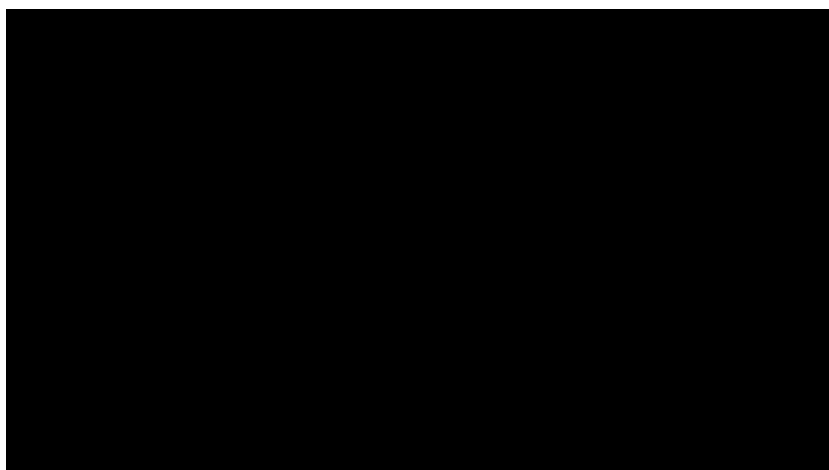
## Adidas – Smart Ball



<http://micoach.adidas.com/>



## Adidas - Smart Ball



<http://micoach.adidas.com/>





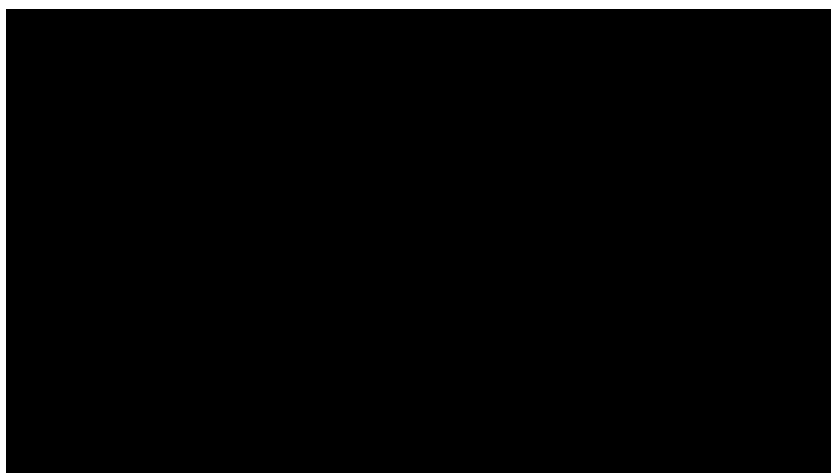
## Bragi – Smart Earphone



<http://www.bragi.com/>



## Bragi – Smart Earphone



<http://www.bragi.com/>



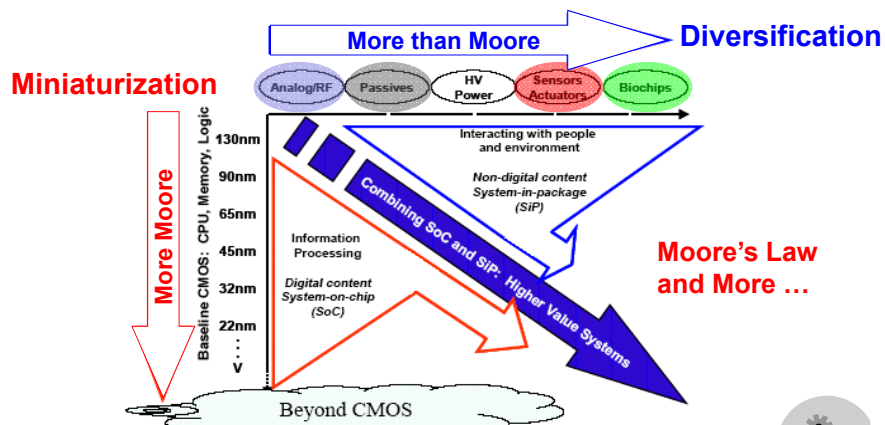
## Why MEMS

- Small and Smart



## Why MEMS

- Small and Smart
- Add value to the existing CMOS tech



Source: ITRS Roadmap 2005, [www.itrs.net](http://www.itrs.net)



## 平面加工技術

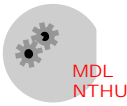
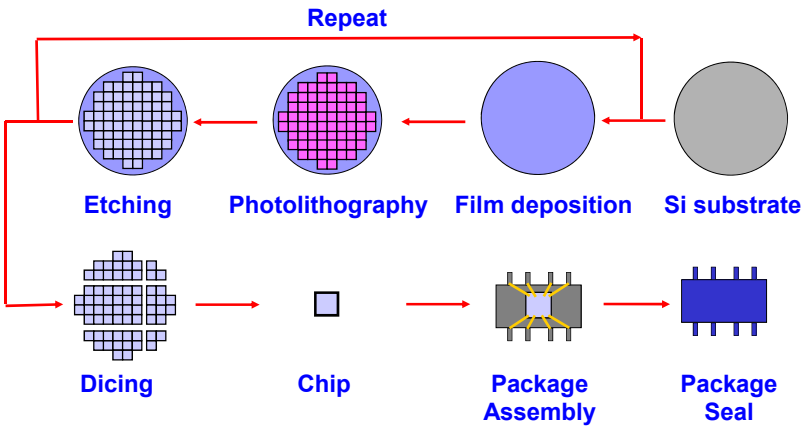


## Planar Technologies

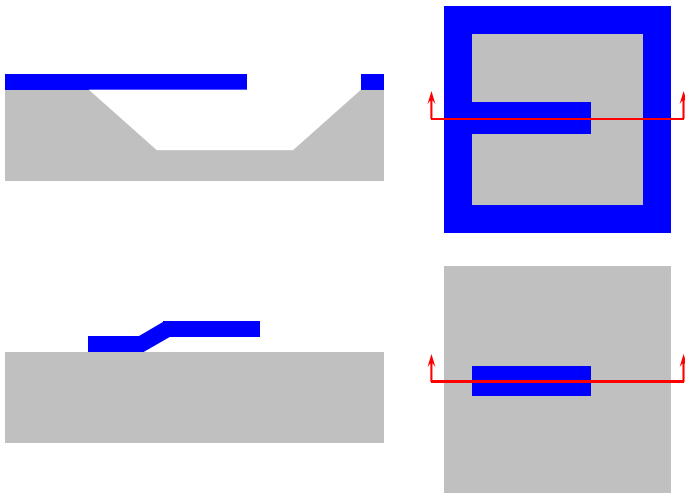
- IC : TSMC, UMC, Vanguard, ...
- LED/VCSEL/Diode laser : Liteon, Epistar,...
- TFT-LCD : AUO, Chimei-Innolux, ...
- Magnetic recording head : Seagate, WD, ...
- **MEMS : TSMC, UMC, APM, ...**



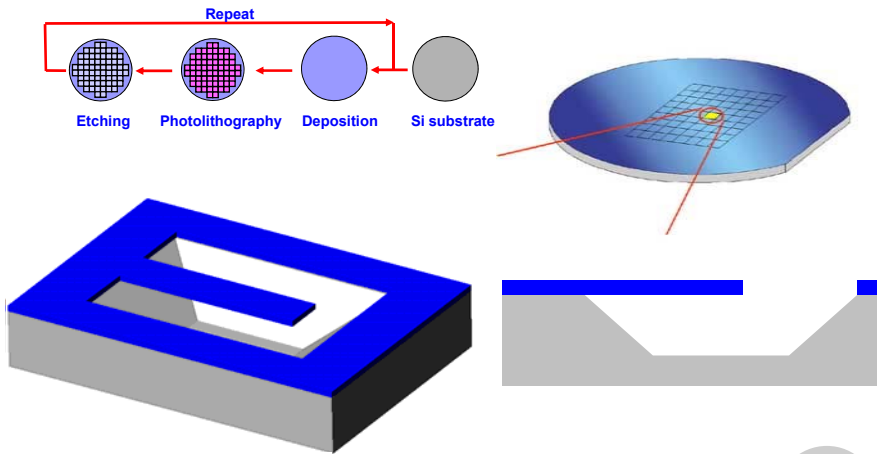
# Semiconductor processes



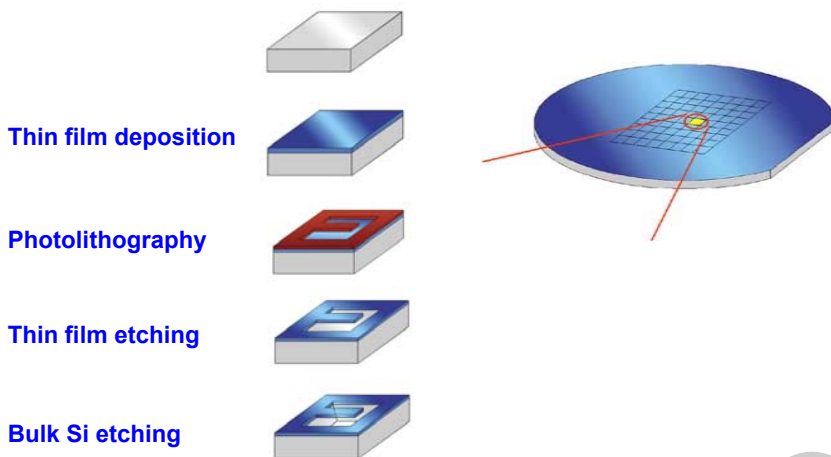
# Suspended MEMS Structures



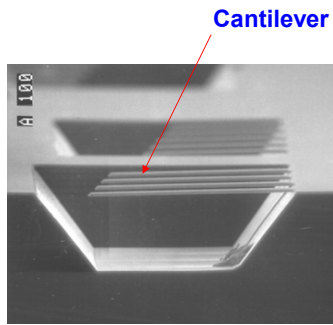
# Bulk Micromachining



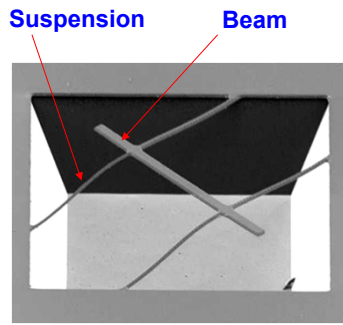
MEMS Technology



• Bulk Micromachined Beams



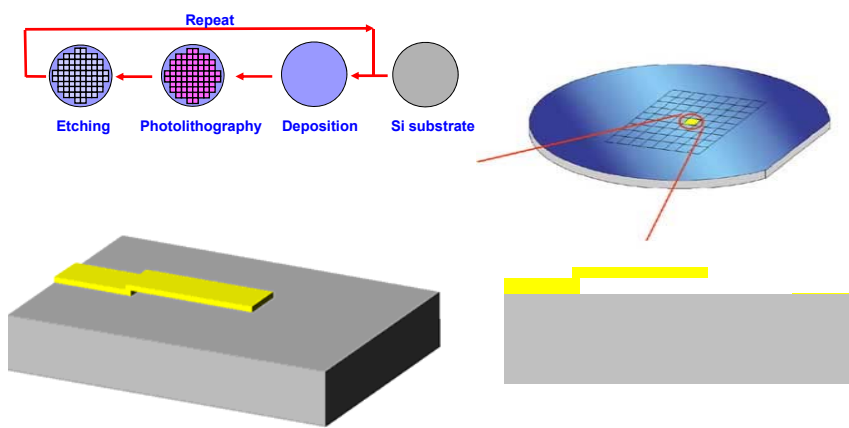
W. Fang, 1994



Yu and Fang, *JMM*, 2005

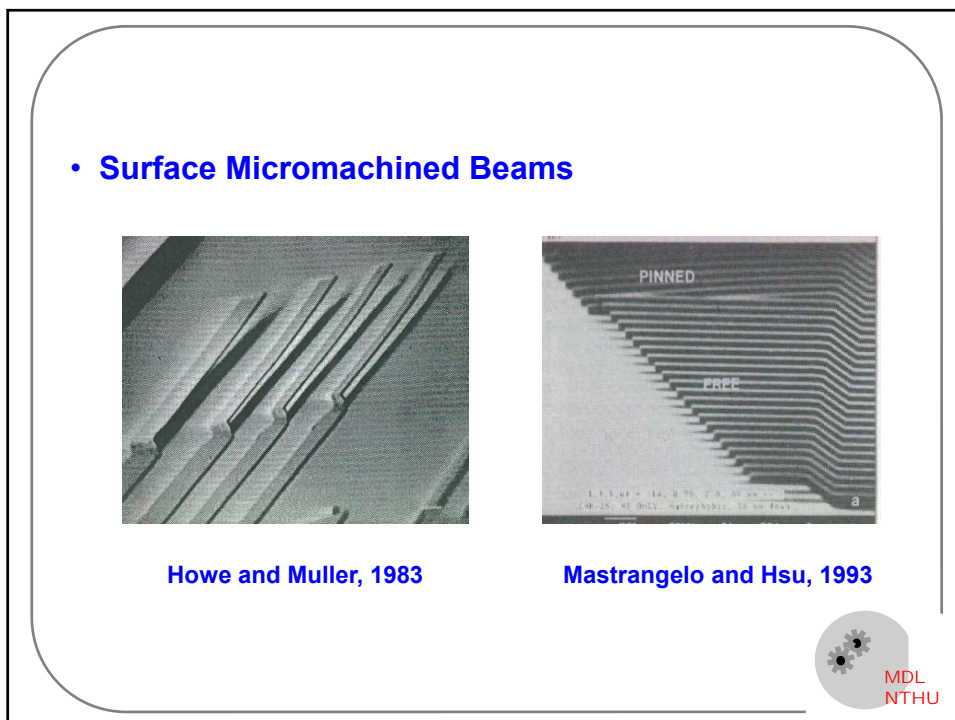
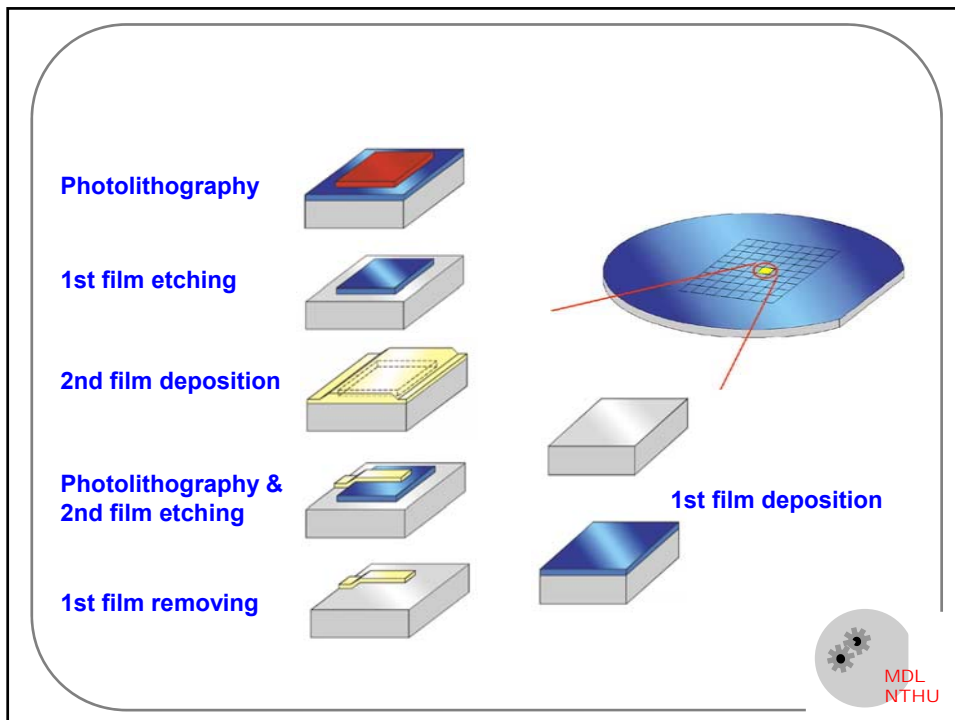


Surface Micromachining



Lithography, Etching, and Deposition

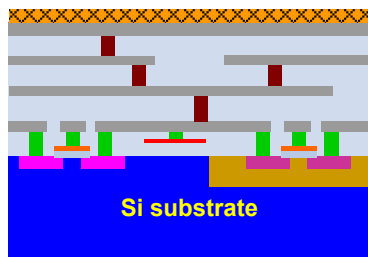




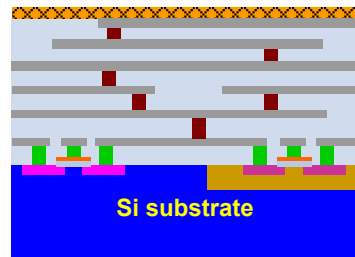
## Semiconductor Devices

- Examples: by CMOS processes at TSMC, UMC, etc...

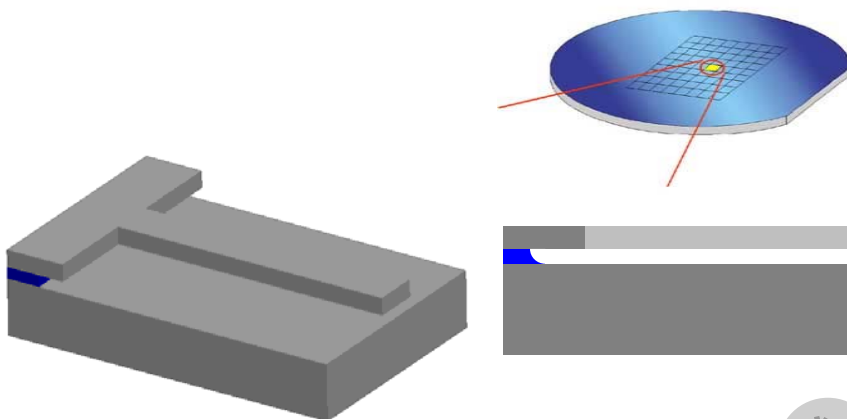
0.35 $\mu\text{m}$  2P4M CMOS process



0.18 $\mu\text{m}$  1P6M CMOS process



## SOI Micromachining

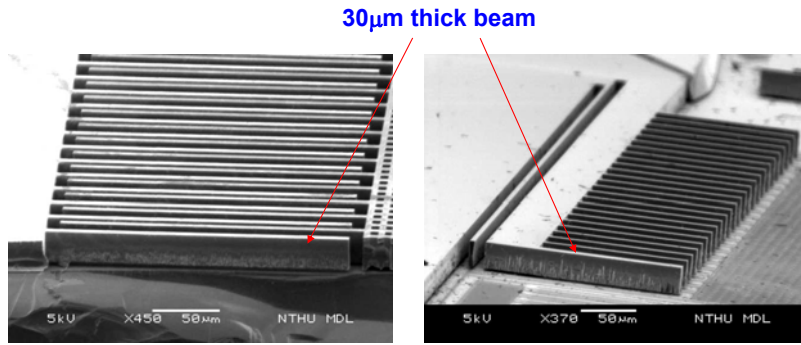


SOI micromachining





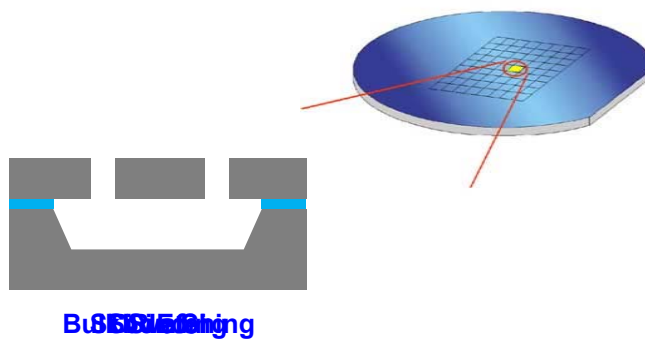
- SOI Micromachined Beams



MDL



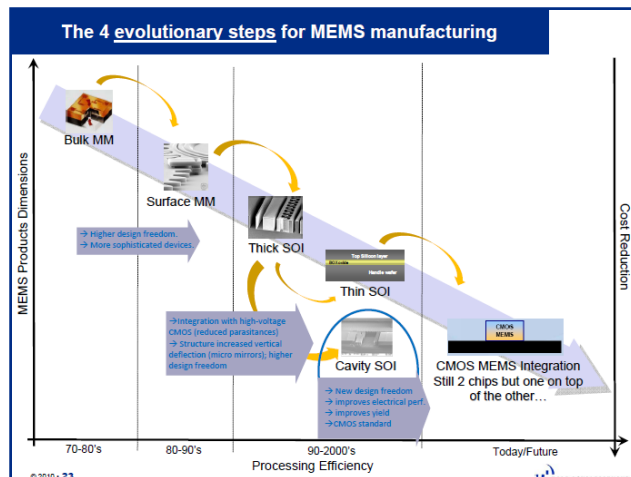
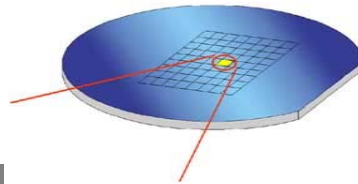
## Cavity SOI Micromachining



# CMOS SOI Micromachining



CMOS SOI Micromachining



Yole's report, 2010



# 關鍵元件

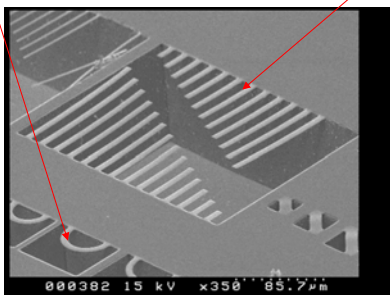


## Passive component

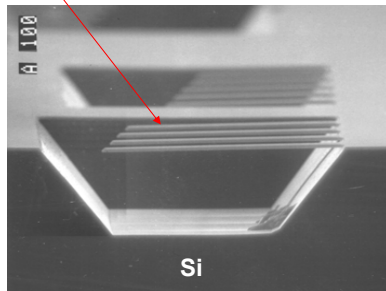
- Cantilever, suspension - springs

Semi-circular suspension

Cantilever



T. Tzou and W. Fang, 1999

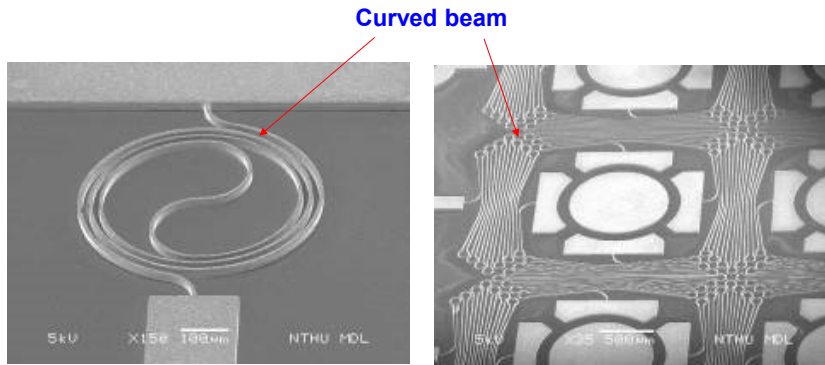


W. Fang, 1994



## Passive component

- Curved beam - spring

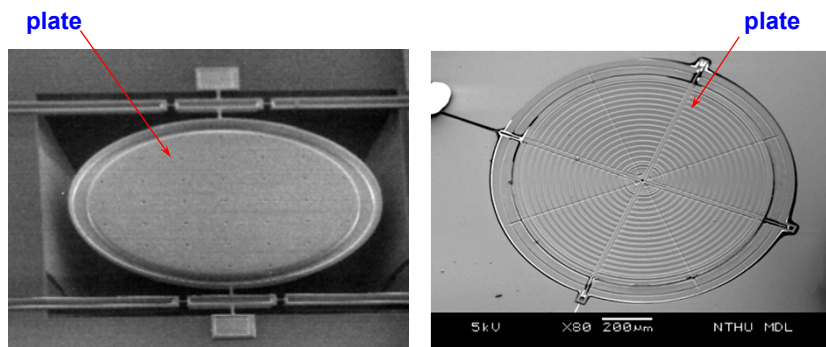


W.-L. Sung and W. Fang, 2014



## Passive component

- Plate – rigid mirror, flexible diaphragm (microphone)



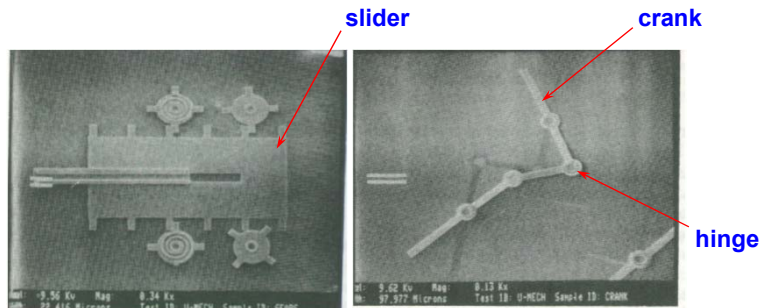
H.-Y. Lin and W. Fang, 2000

C.-K. Chan and W. Fang, 2011



## Passive component

- Slider, hinge, cranks

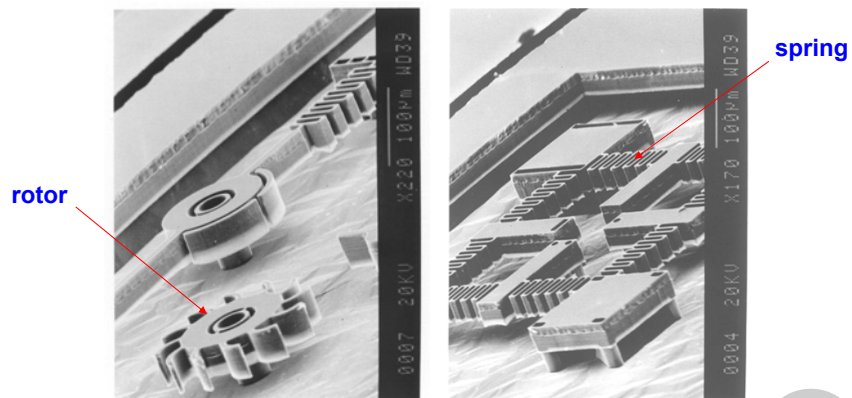


L.-S. Fan, et. al., IEEE Transaction on ED, 1988



## Passive component

- Gear, rotor, linkage

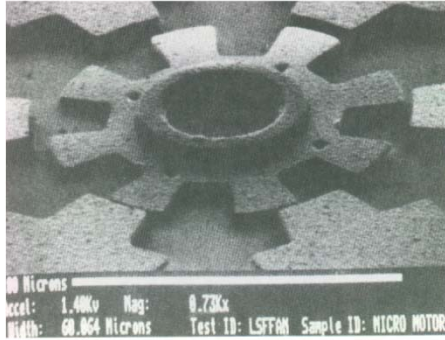


J. Hsieh and W. Fang, 2000



## Active component

- Angular electrostatic actuator - motor

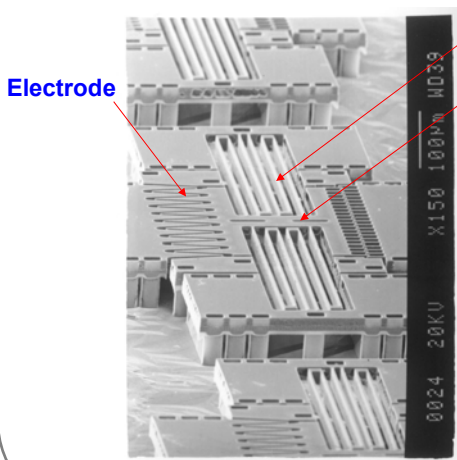


L.-S. Fan, et.al., Int. Electron Devices meeting, 1988

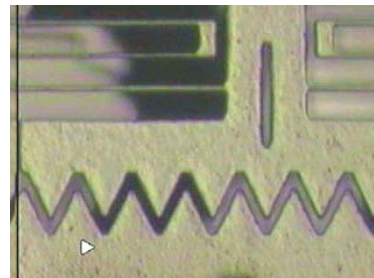
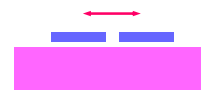


## Active component

- Linear electrostatic actuator



Spring  
Moving stage

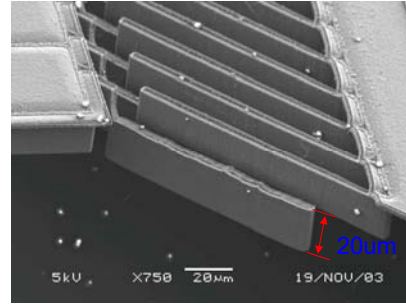
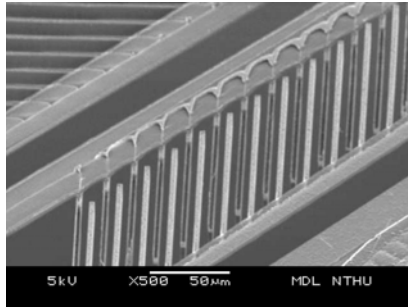
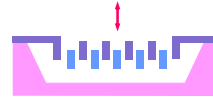


J. Hsieh and W. Fang, 2000



## Active component

- Linear electrostatic actuator



M. Wu and W. Fang, 2005



## Active component

- Angular electrostatic actuator

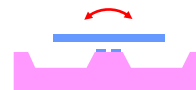
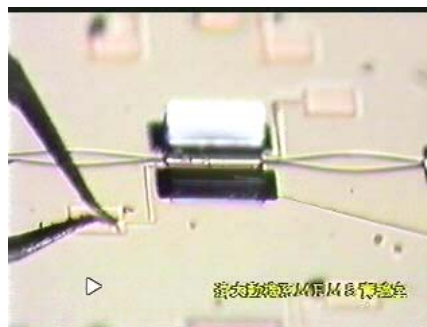
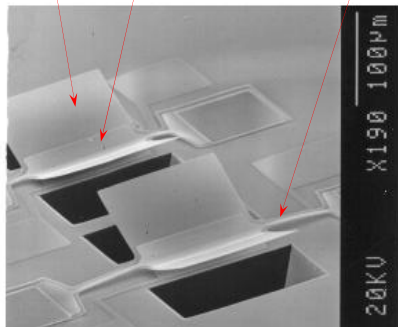


Plate Electrode Spring

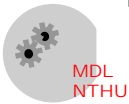
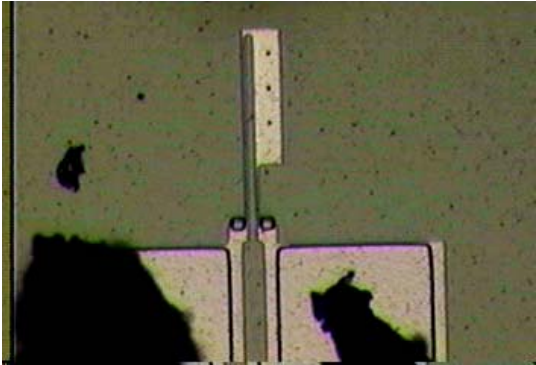


J. Hsieh and W. Fang, *Sensors and Actuators A*, 2000



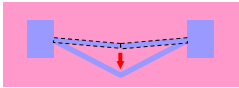
# Active component

- Linear thermal actuator



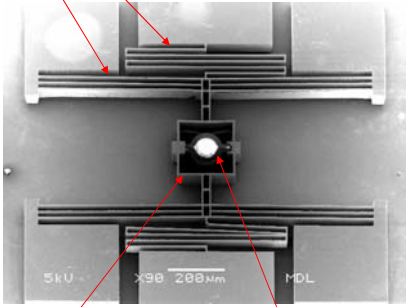
# Active component

- Linear thermal actuator



Spring (passive)

V-beam actuator (active)



Supporting frame (passive)

Lens (passive)

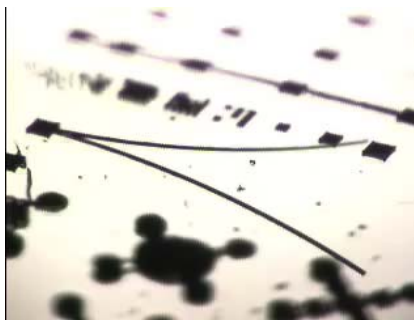
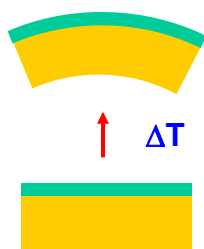
C. Lai, J. Hsieh, and W. Fang, *IEEE Optical MEMS'04*, 2004





## Active component

- Linear thermal actuator

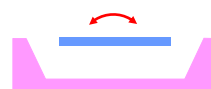
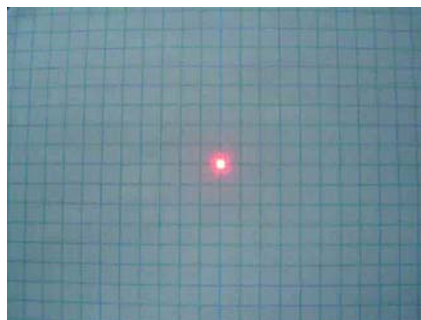
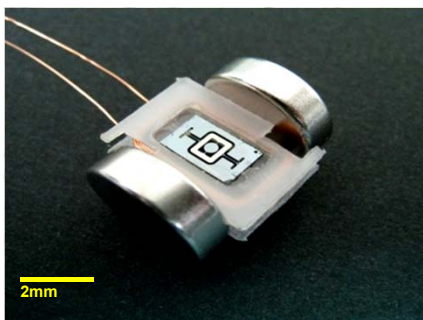


W.-K. Hsu, and W. Fang, *Nanotech*, 2008



## Active component

- Angular magnetic actuator



Yang, and Fang, *JMEMS*, 2007



# 組裝與整合



## About Mechanical Device



<https://www.patek.com/>



## About Mechanical Device



<https://www.patek.com/>



## Assembly



[www.precisionscalereplicas.com](http://www.precisionscalereplicas.com)



[www.kukausa.com](http://www.kukausa.com)



## Assembly

- Toyota and Foxconn assembly lines



[www.youngertoyota.com](http://www.youngertoyota.com)



[www.zaeke.com](http://www.zaeke.com)



## Assembly

- Boeing 777 assembly lines



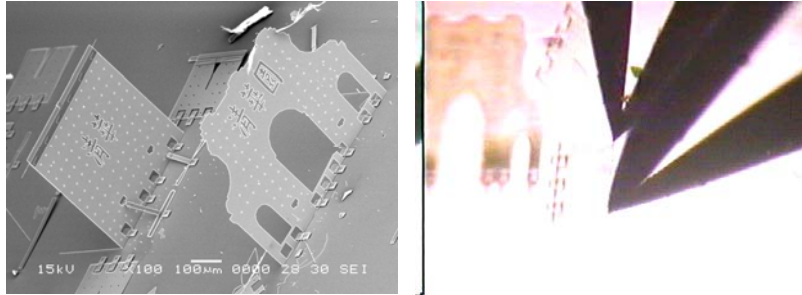
[www.ainonline.com](http://www.ainonline.com)



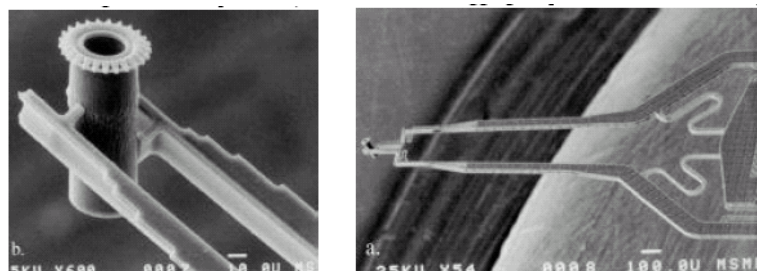
[www.flightglobal.com](http://www.flightglobal.com)



- **Manually assembled by probe**



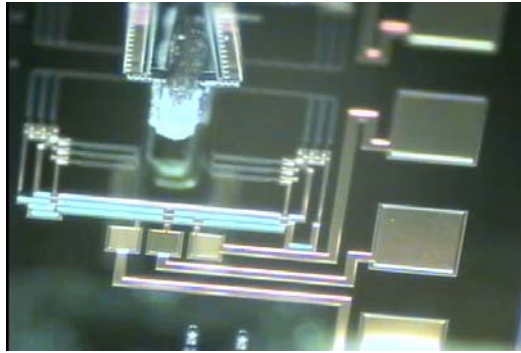
- **Manually assembled by micro gripper**



**Keller, UC Berkeley, 1998**



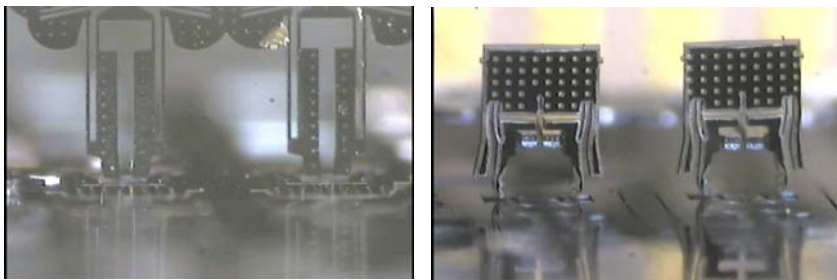
- **Automatically assembled by precision machine**



Zyvex Inc.



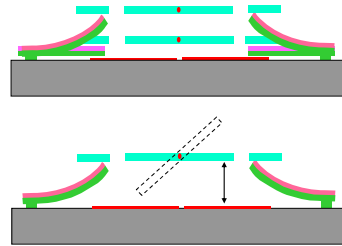
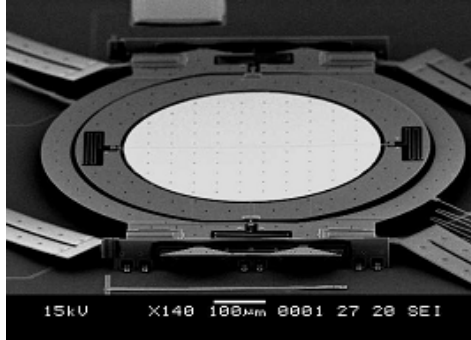
- **Automatically assembled by precision machine**



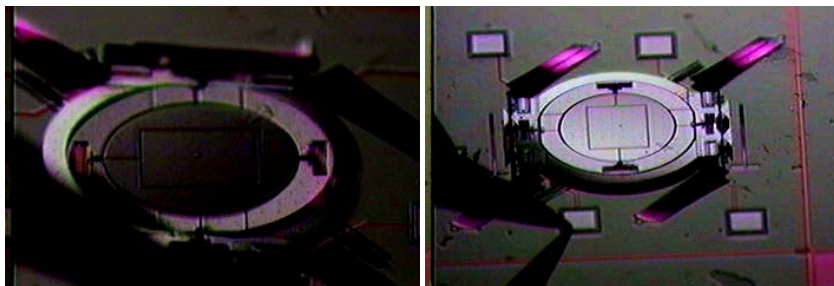
Zyvex Inc.



- Self assembly by residual stress deformed beam



Y.-P. Ho, M. Wu, H. Lin, and W. Fang, *IEEE Optical MEMS '02, 2002*

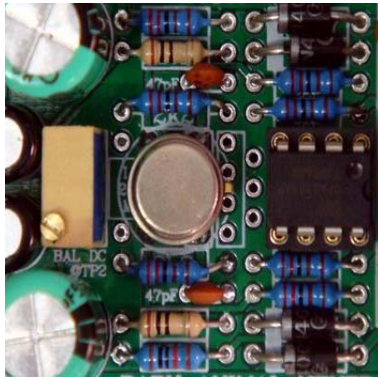


Y.-P. Ho, M. Wu, H. Lin, and W. Fang, *IEEE Optical MEMS '02, 2002*

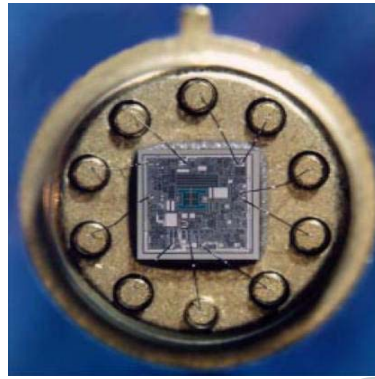


## Process Integration

- **Discrete vs Integrated** electronics components



ATM Elektro, Czech Republic



ADI, USA



- **Assembly by process integration (一體成形)**

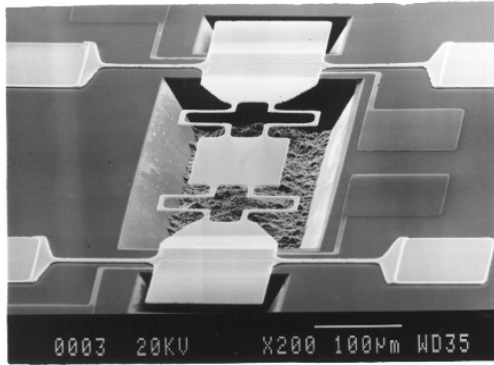


Brigham Young Univ., USA





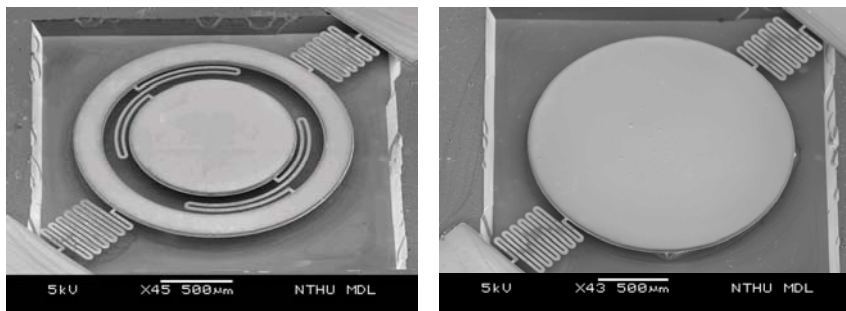
- Assembly by process integration



J. Hsieh and W. Fang, *Transducer'99*, 1999



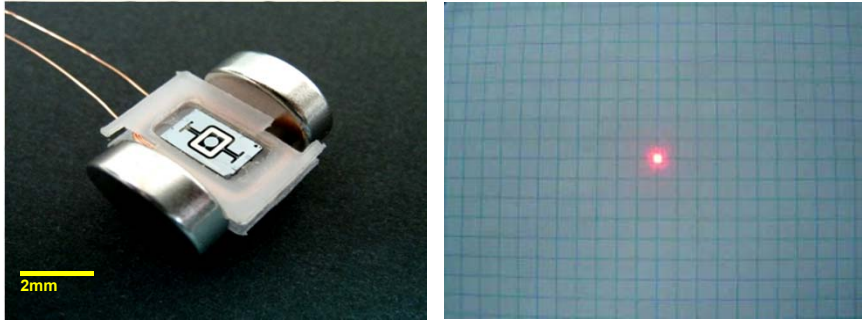
- Assembly by process integration



H. Yang, and W. Fang, *IEEE MEMS'06*, Istanbul, Turkey, 2006



• Scanning images



Yang, and Fang, *JMEMS*, 2007



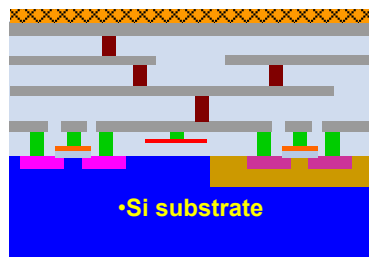
製程平台 - 標準製程



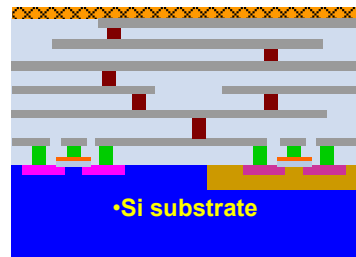
## Standard CMOS Processes

- Available in CMOS foundries: TSMC, UMC, etc...

0.35 $\mu$ m 2P4M CMOS process

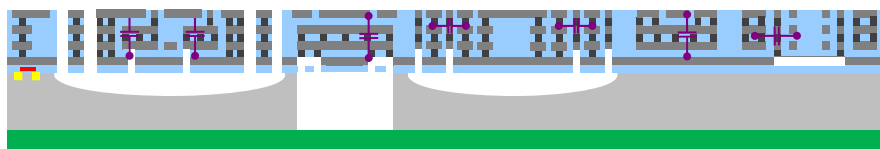


0.18 $\mu$ m 1P6M CMOS process

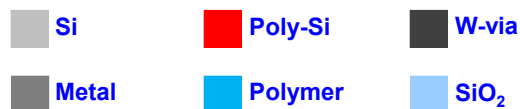


## CMOS-MEMS Platform

Sensing circuit    Tri-axis G sensor    Pressure sensor    Magnetic sensor    Tactile sensor    RF resonator



Standard TSMC 0.35 $\mu$ m 2P4M CMOS process



- Standard TSMC 0.35 $\mu$ m 2P4M CMOS process
- Post-CMOS processes developed by Prof. Fang's group



### 3-axis G-sensor

**Single proof mass**

Sun, and Fang, *IEEE MEMS*, 2009  
Sun, and Fang, *IEEE Trans. on ED*, 2010

MDL  
NTHU

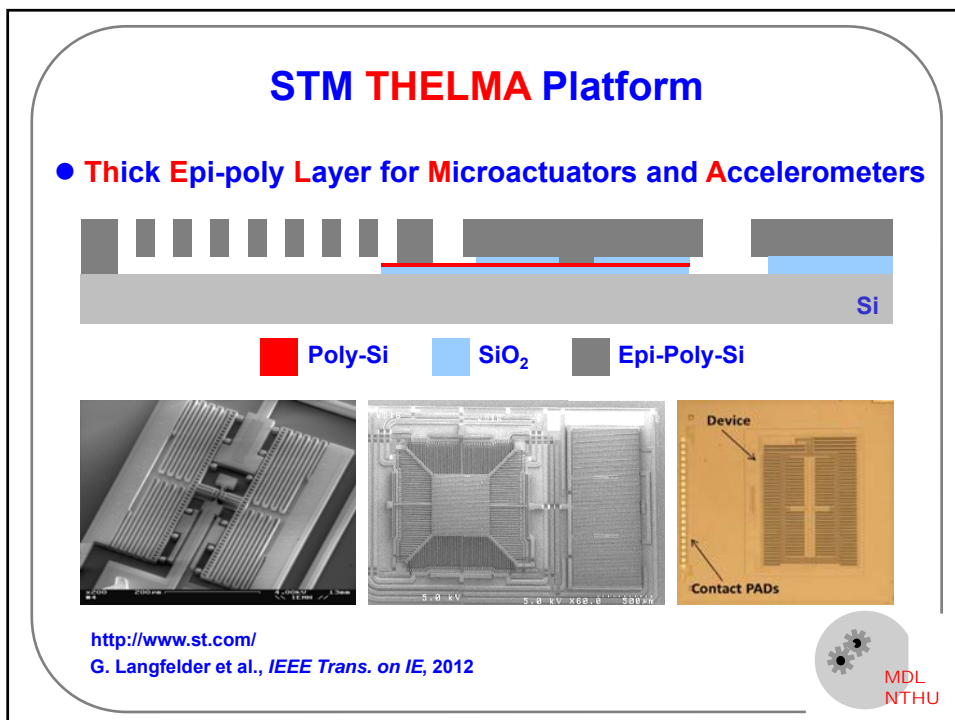
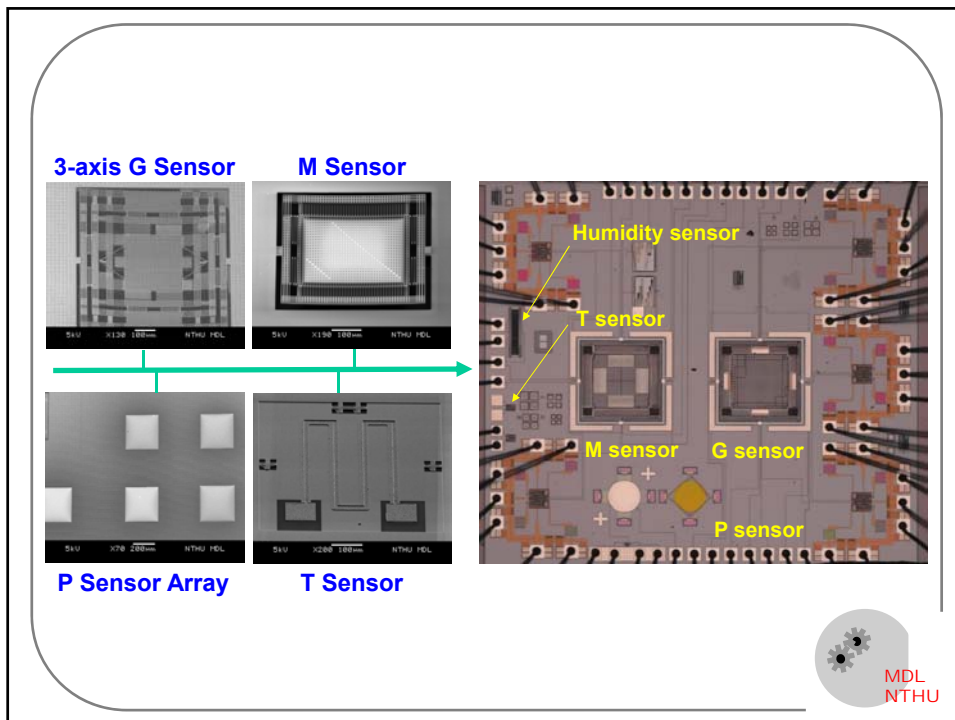
### Pressure Sensors

**Suspended diaphragm**      **Packaging**

**FIB sectioning**

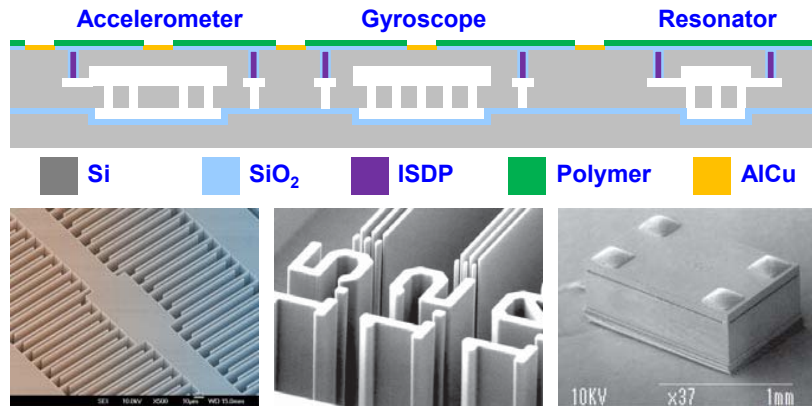
Sun, and Fang, *Transducers*, 2009  
Sun, and Fang, *JMM*, 2009

MDL  
NTHU



## Teledyne DALSA MIDIS Platform

- MEMS Integrated Design for Inertial Sensors

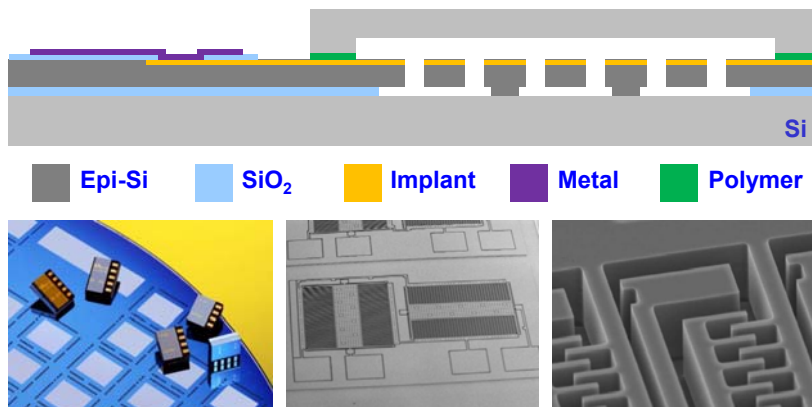


<http://www.teledynedalsa.com/>



## Tronics Platform

- Epi-SOI technology

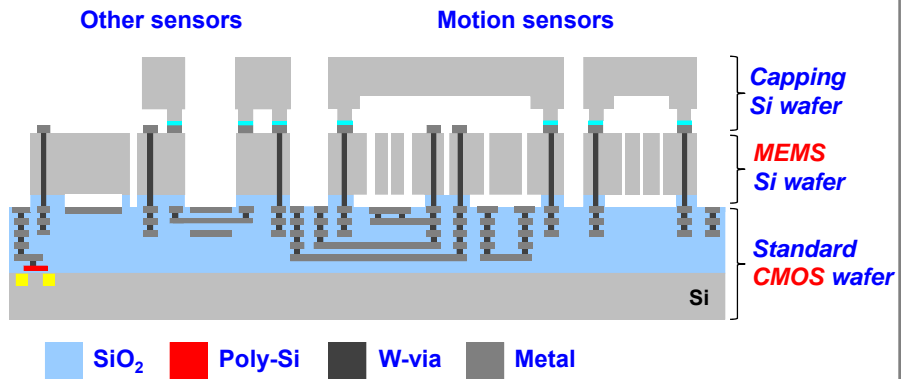


<http://www.tronicsgroup.com/>  
S. Renard, *JMM*, 2000



## TSMC MEMS Platform

- Si-MEMS above CMOS



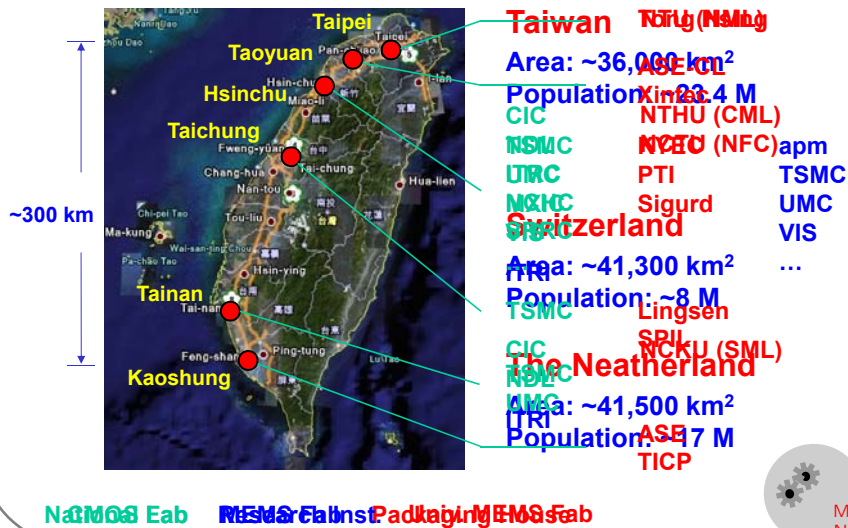
Source : TSMC



## 台灣現況簡介

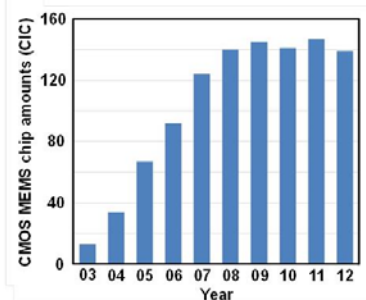


## MEMS Eco-system at Taiwan



## National Lab – CIC (TSRI)

- **CIC: Chip Implementation Center, since 1993**
- **CMOS MEMS Processes**
  - + 0.35μm 2-Poly 4-Metal **TSMC** process (from 2002, 4 runs/year)
  - + 0.18μm 1-Poly 6-Metal **TSMC** process (from 2006, 4 runs/year)
  - + 0.18μm 1-Poly 7-Metal **UMC** process (from 2013, 2 runs/year)
- **APM post-CMOS Process to release MEMS designs**



Source : CIC



## National Lab – NDL (TSRI)



- NDL: **N**ano **D**evice **L**aboratories, since 1988
- NDL has been dedicated to:
  - + Support academic research  
(More than 70 equipments are opened to students )
  - + Frontier IC/MEMS technology development
  - + Bridging the academic and industry



Clean room areas (m<sup>2</sup>)

Class 10	370
Class 1,000	250
Class 10,000	1525
Facilities area	1420



## Nonprofit Research Org - ITRI



- ITRI: **I**ndustrial **T**ech. **R**esearch **I**nst., since 1973
- Manpower: ~6,000
  - + ~200 MEMS engineers/researchers
- **M**icrosystems **T**ech **C**enter: **M**EMS total solution
- **P**ilot-run **M**EMS **F**ab: **M**EMS/post-CMOS processes

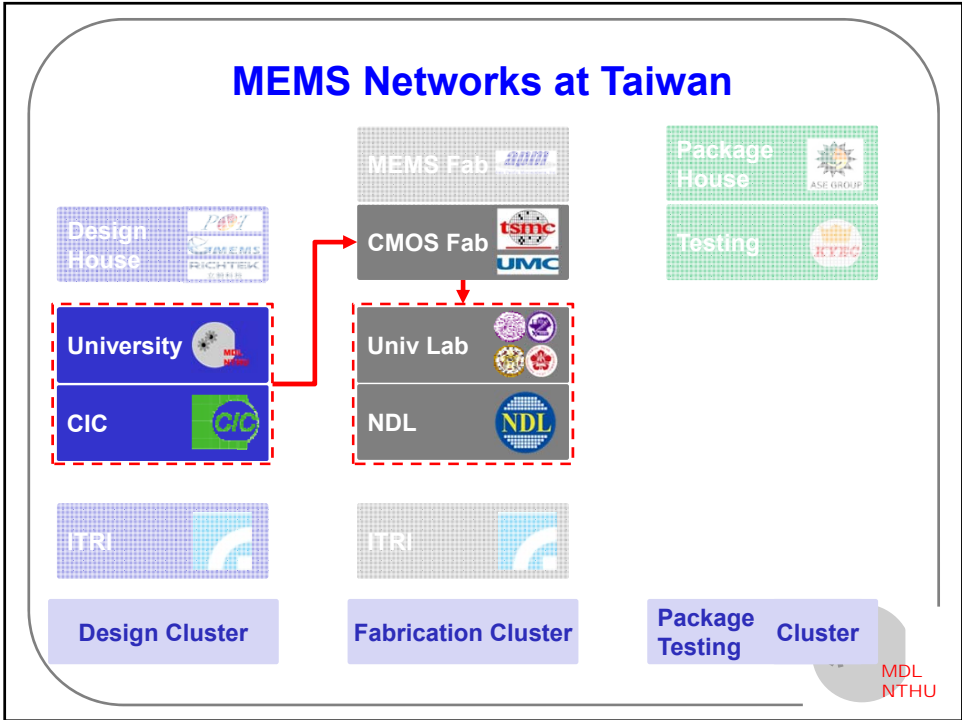
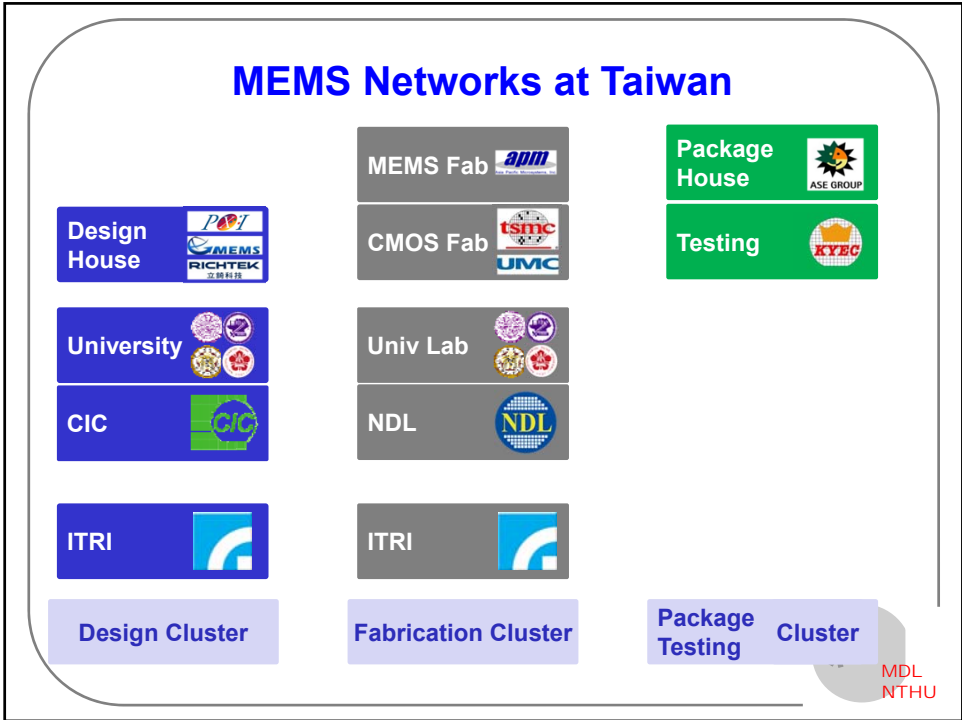


**MEMS** clean room areas (m<sup>2</sup>)

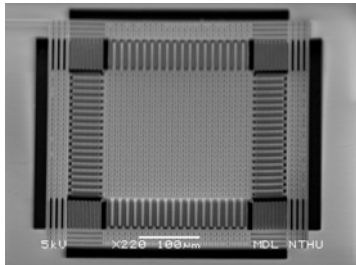
Class 10	<b>N/A</b>
Class 1,000	<b>260</b>
Class 10,000	<b>390</b>
Facilities area	<b>360</b>

Source : ITRI Southern Region Campus

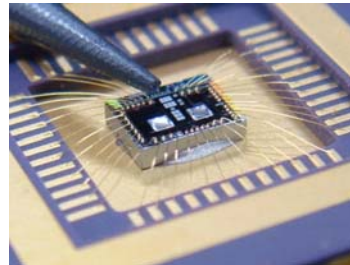




## 0.18um 1P6M TSMC CMOS Process



3-axis accelerometer

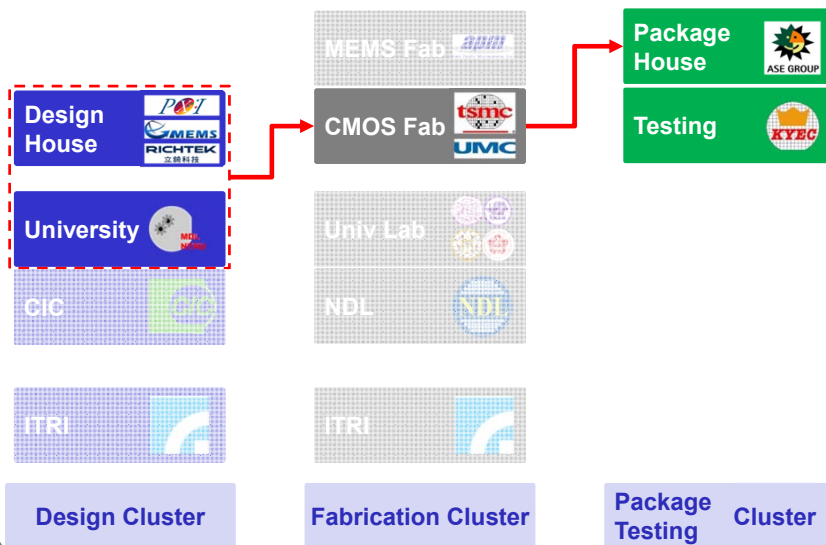


Sensor after bonding

Sensing-axis	X-axis	Y-axis	Z-axis
Measurement Range (G)	0.01~1	0.01~1	0.01~1
Sensitivity (mV/G)	14.2	14.6	8.0
Non-linearity (%)	3.0%	1.5%	1.8%
Noise (mG/sqrtHz)	1.9	2.9	3.4

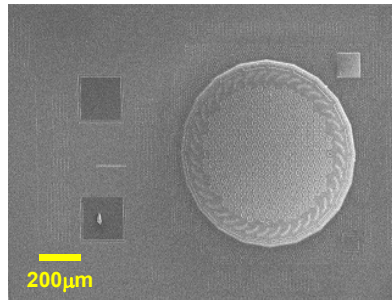


## MEMS Networks at Taiwan

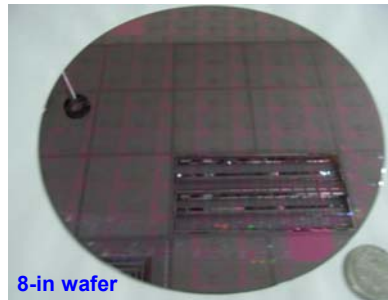


## MEMS Sensor – Design Houses

- **UMC CMOS processes: 8-inch 0.18um 1P6M process**



Microphone by M design house

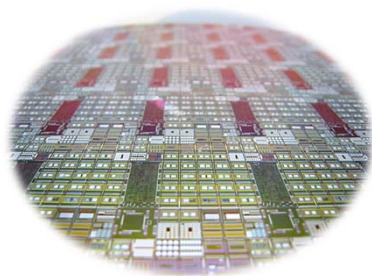


G-sensor by P design house

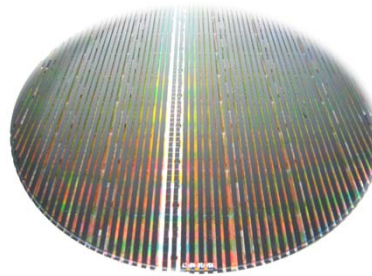


## MEMS Sensors - Ecosystems

- **CMOS MEMS sensors on 8-inch wafer**
- **Eco-systems: ITE/Univ - UMC - SPIL - KYEC**

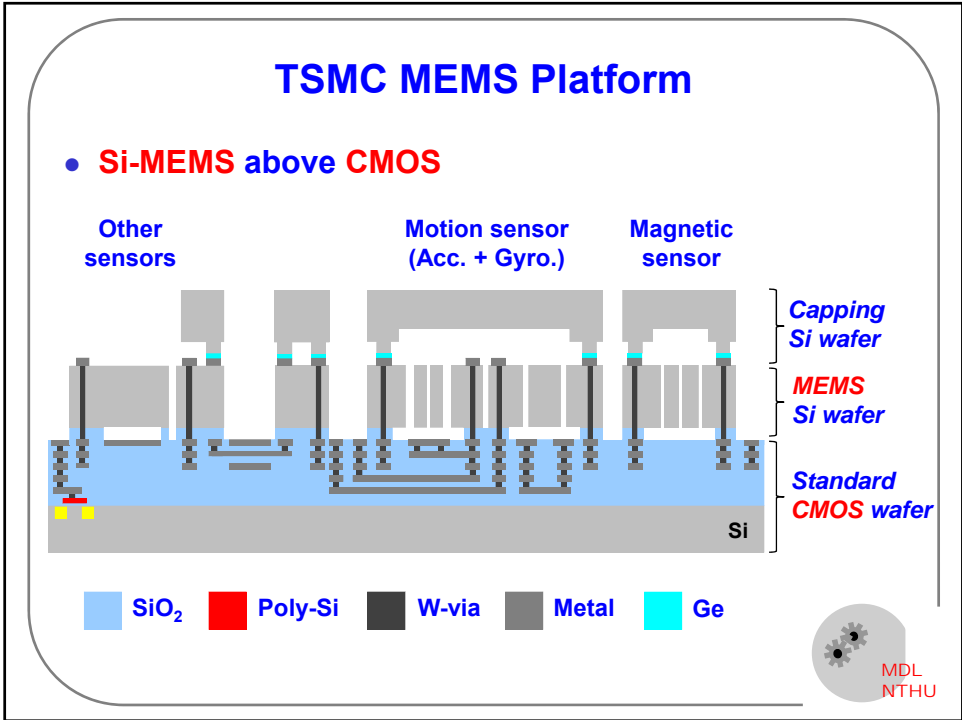
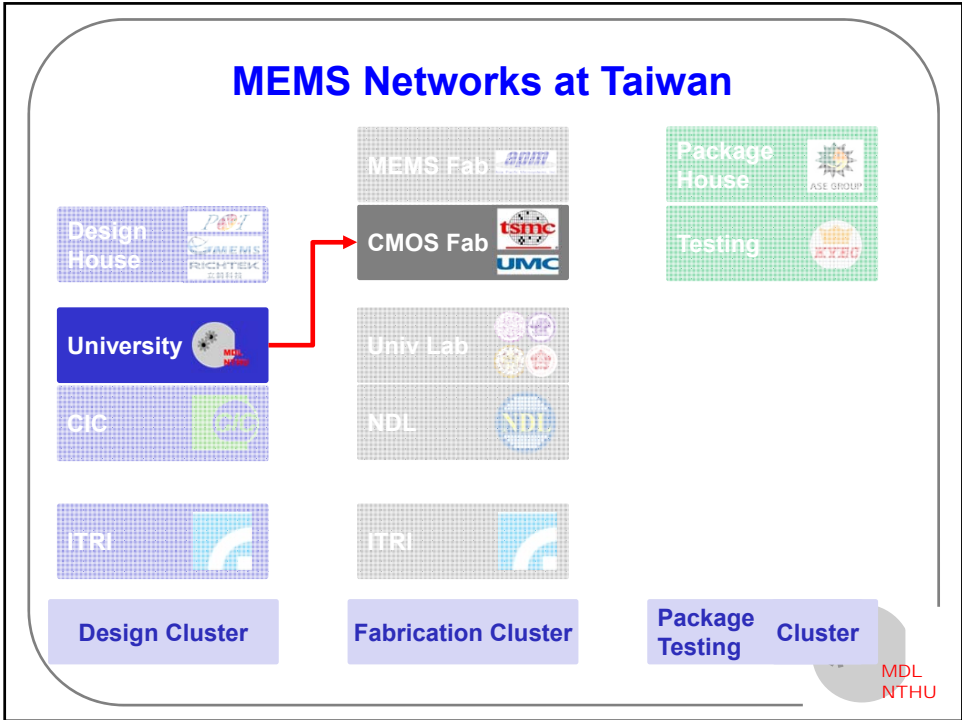


CMOS MEMS on 8" Wafer



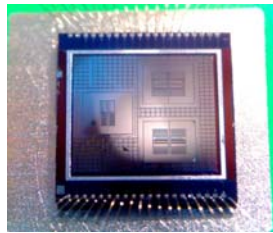
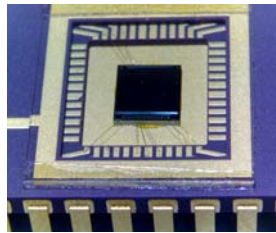
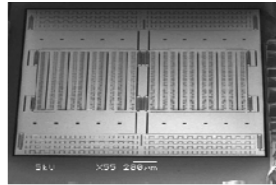
Capped CMOS MEMS Sensors





# TSMC MEMS Platform

- Gyroscope and Magnetic Sensor



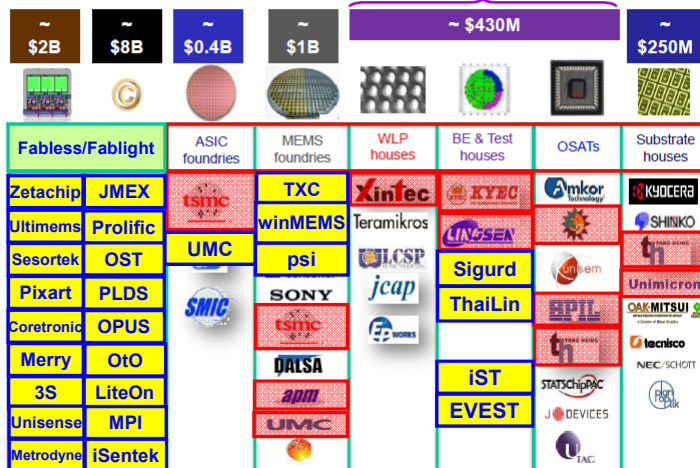
Lee and Fang, *IEEE MEMS*, 2016

Sung and Fang, *IEEE MEMS*, 2016



## 2011 Key MEMS Player Activity Estimate

outsourced packaging assembly, test & calibration



© 2012 - 21

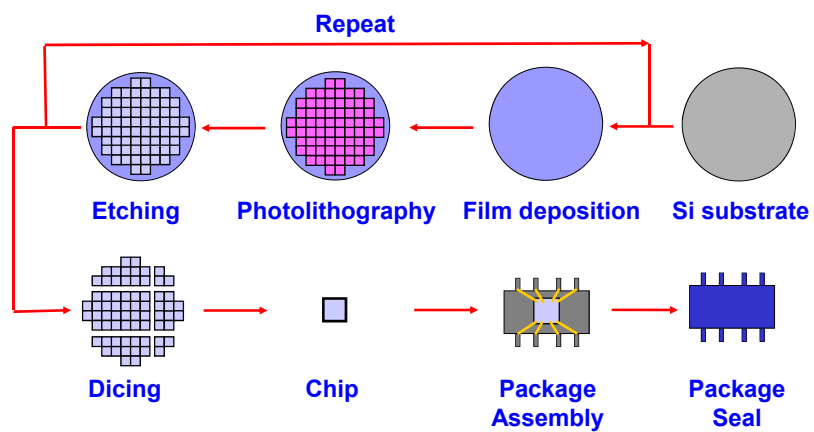
Yole report, SEMICON Taiwan 2012



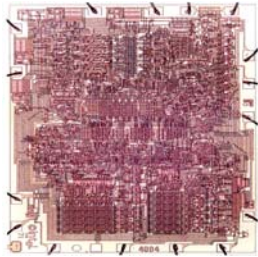
# 結論



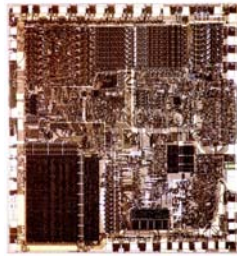
## Semiconductor processes



## Microprocessor



The 4004 – **2.3k**  
transistors, 1971



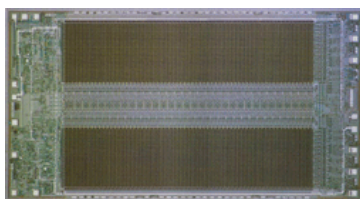
8088/8086 - **29k**  
transistors, 1978



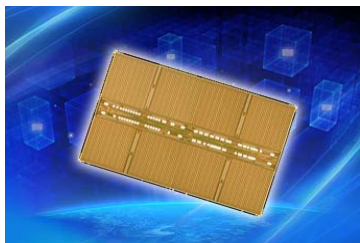
Pentium IV – **42M**  
transistors, 2000



## Memory



The 16kb DRAM, 1976

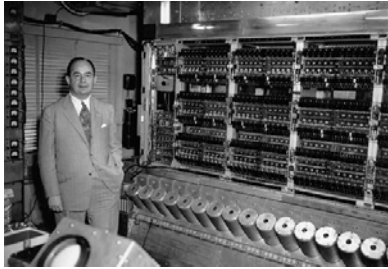


The 2Gb DRAM, 2011

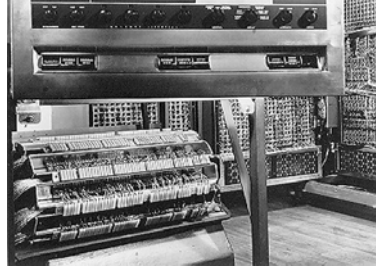




## Computer



von Neumann and his  
"computer", 1952



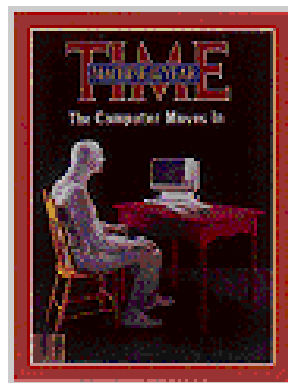
IBM 650, 1954



## Computer

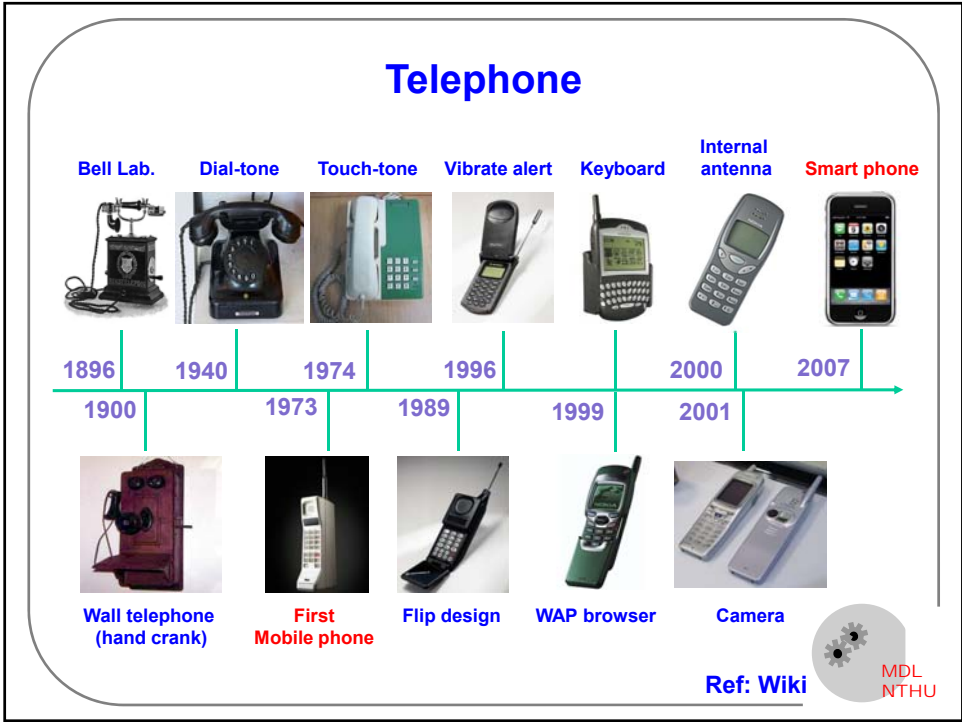
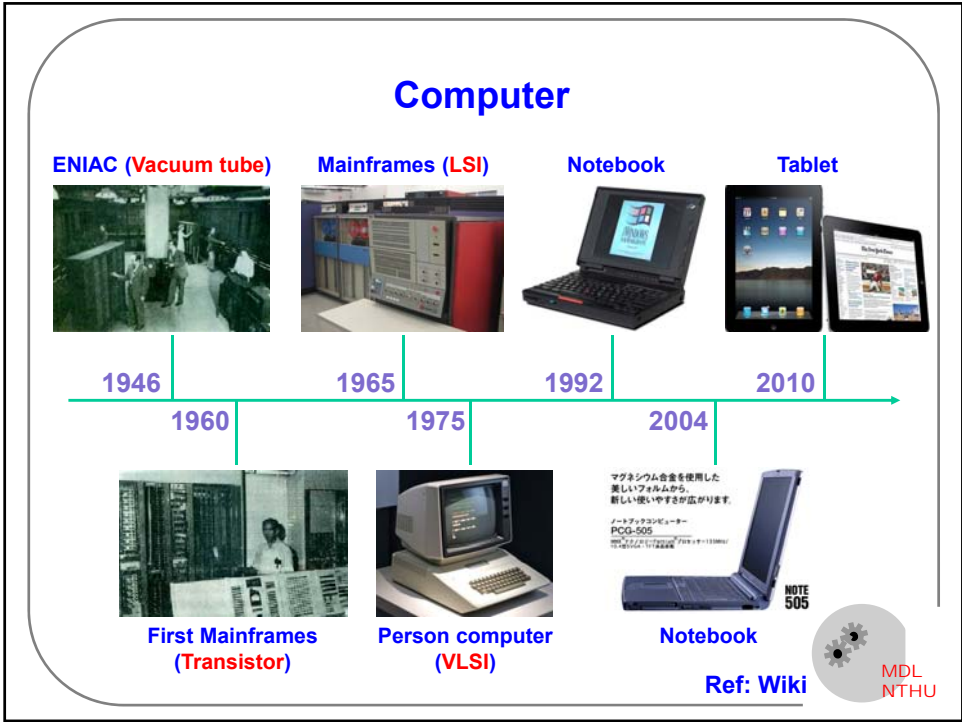


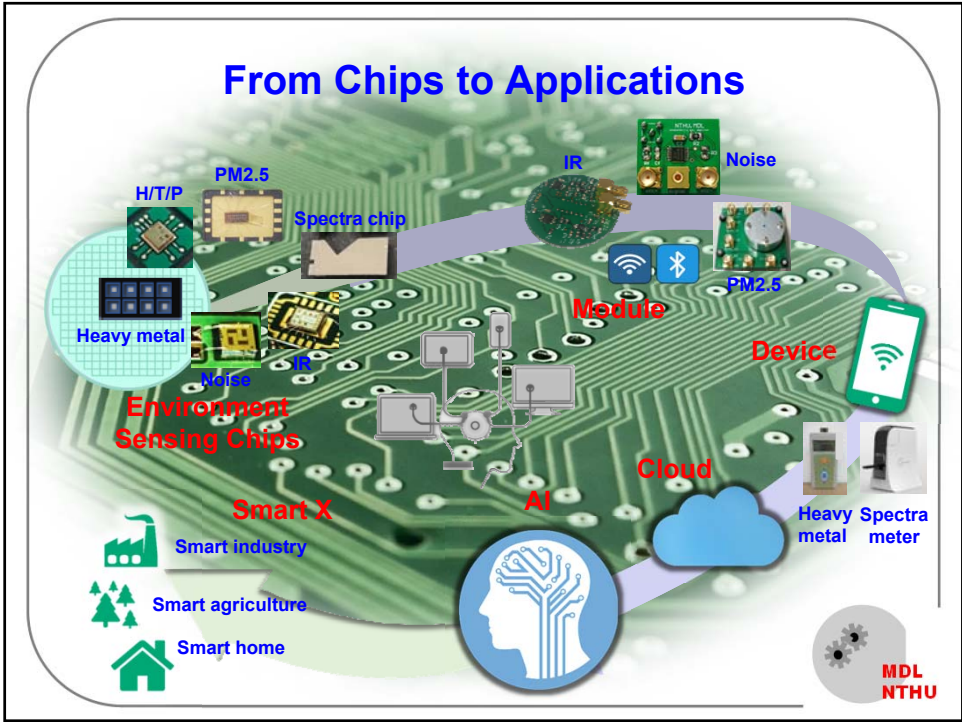
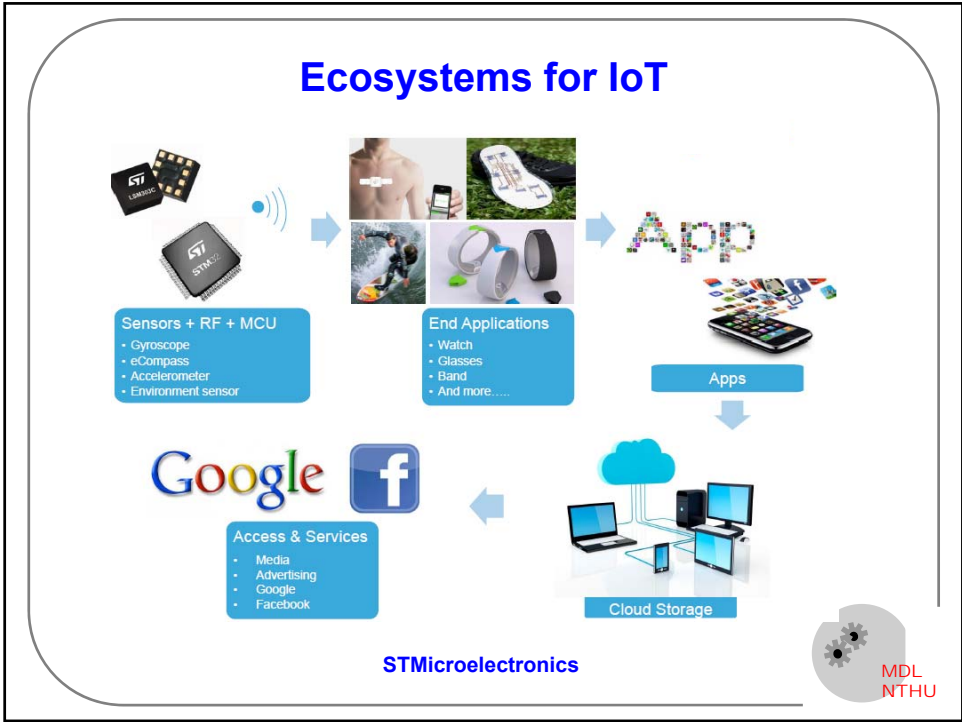
Jobs & Wozniak with Apple II - 1976

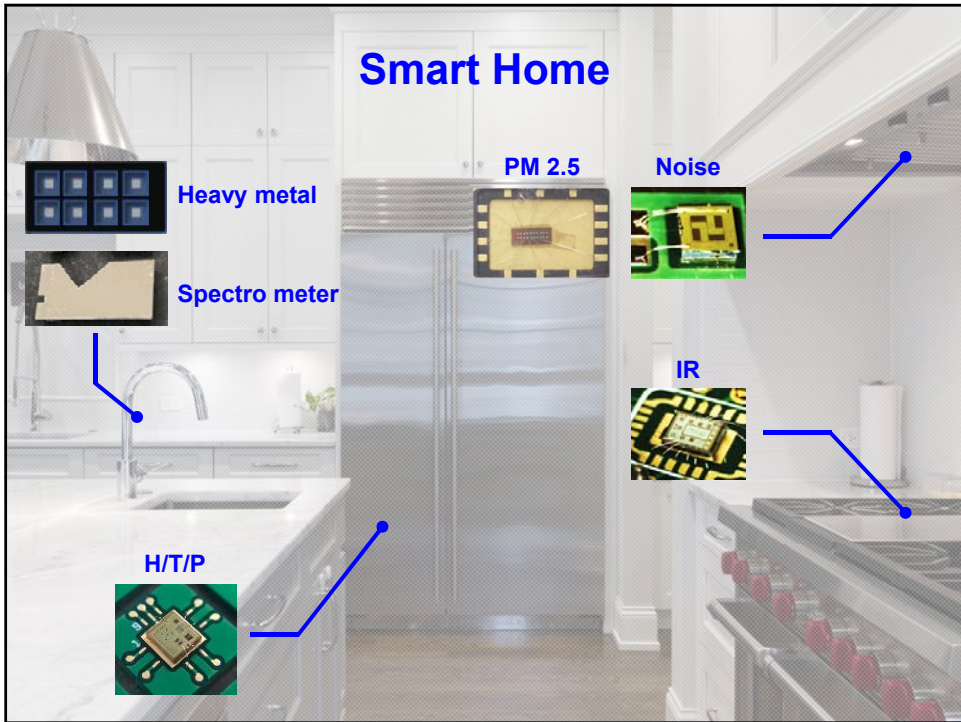
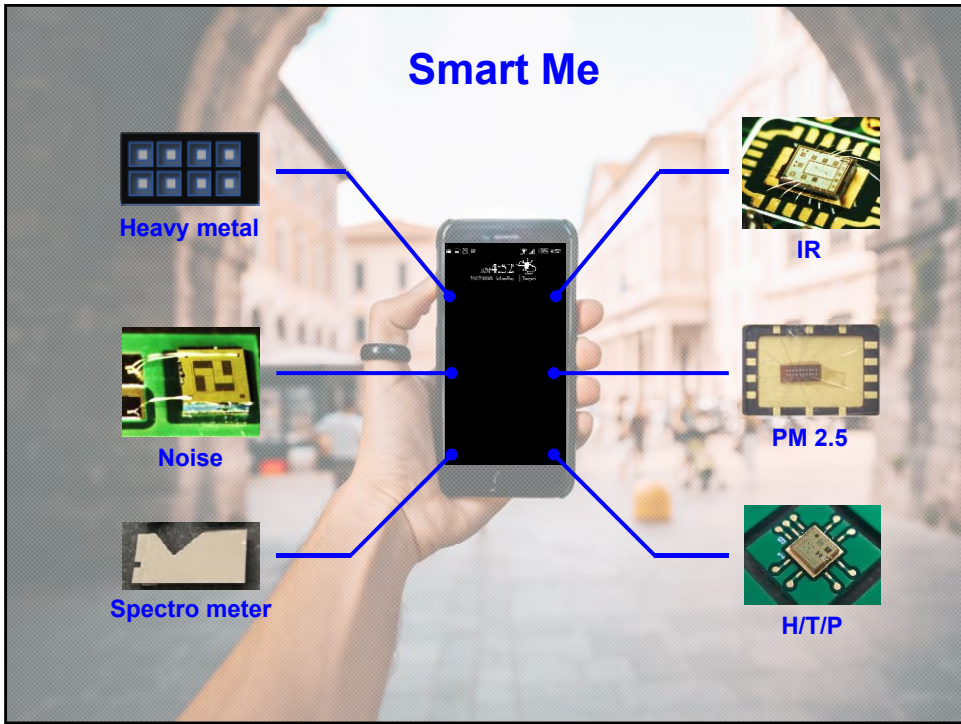


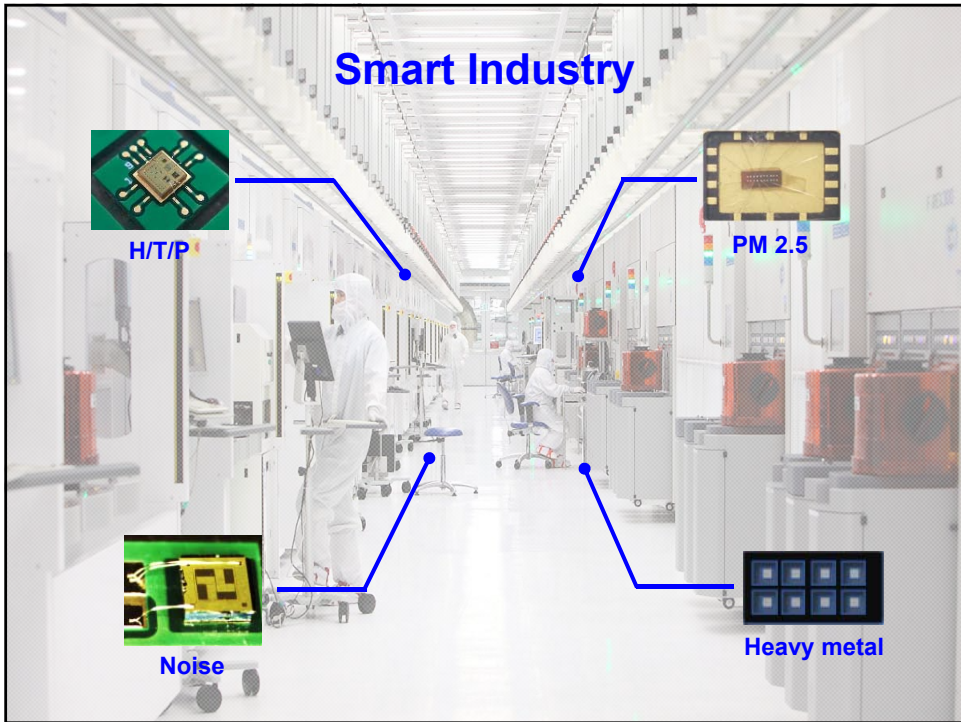
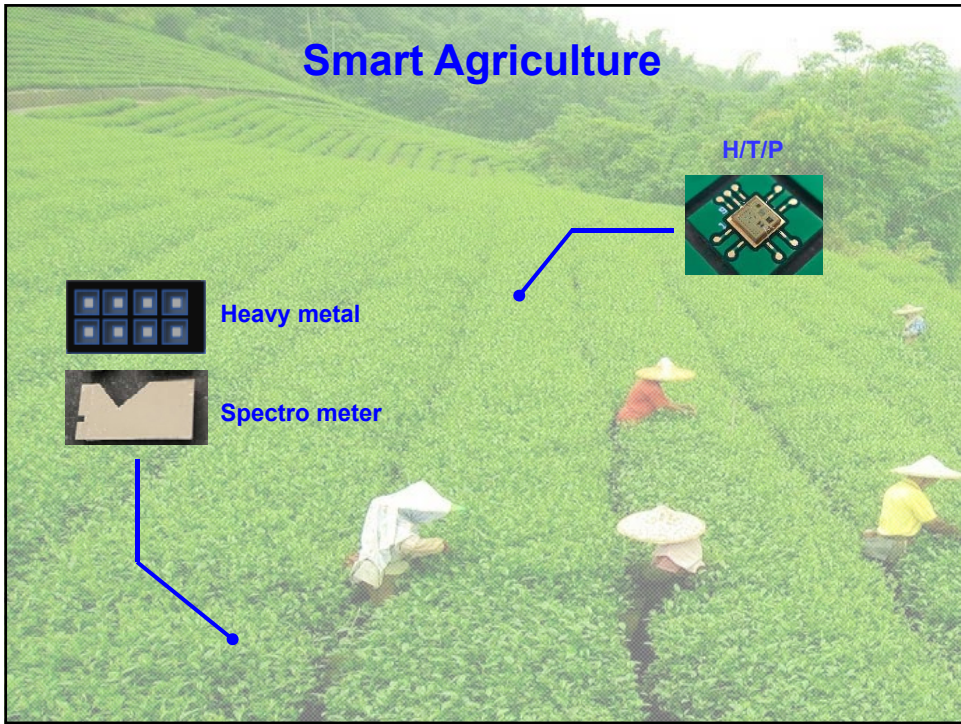
IBM PC – 1981/2

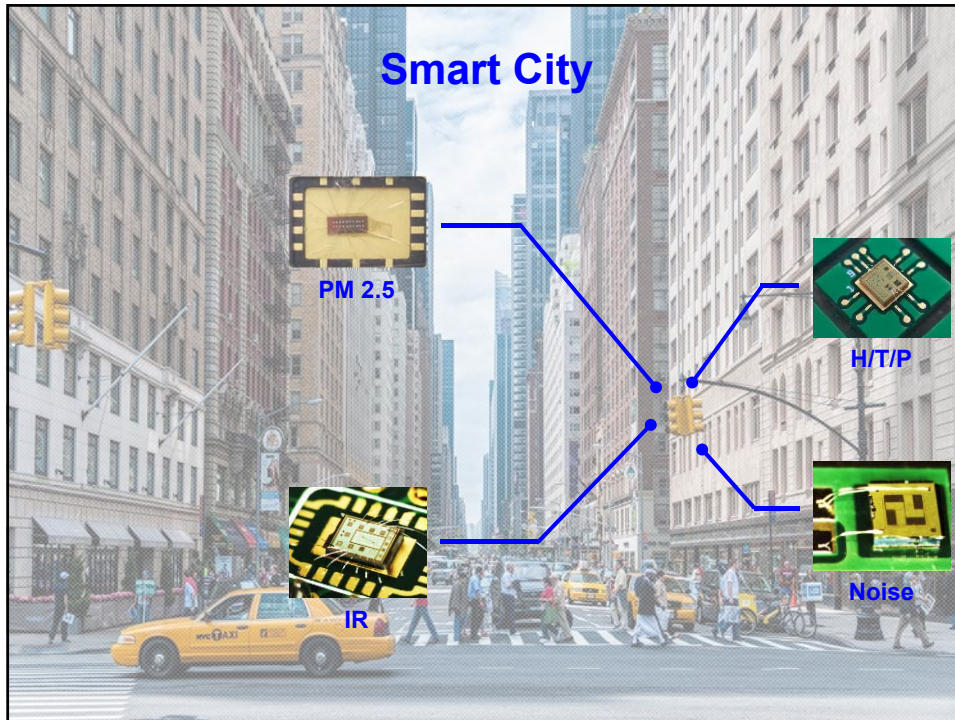












## **IoT – the Next Big Things**

- **The next big things**
  - + Highlight by Dr. Morris Chang of TSMC in 2014
  - + Major players: Google, Apple, Cisco, Alibaba, Huawei, etc.
  - + **Semiconductor remain the key enabling tech.**



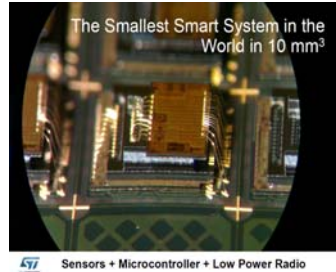
[www.appledaily.com.tw](http://www.appledaily.com.tw)



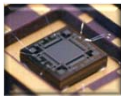
## Semiconductor: Key Tech for *IoT*

- Key Techs for IoT

- + MEMS and Sensors
- + Advanced packaging
- + Ultra low power



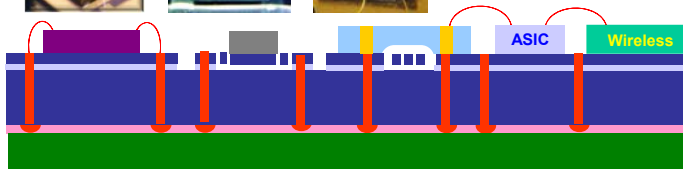
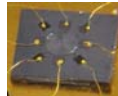
G sensor



Humidity



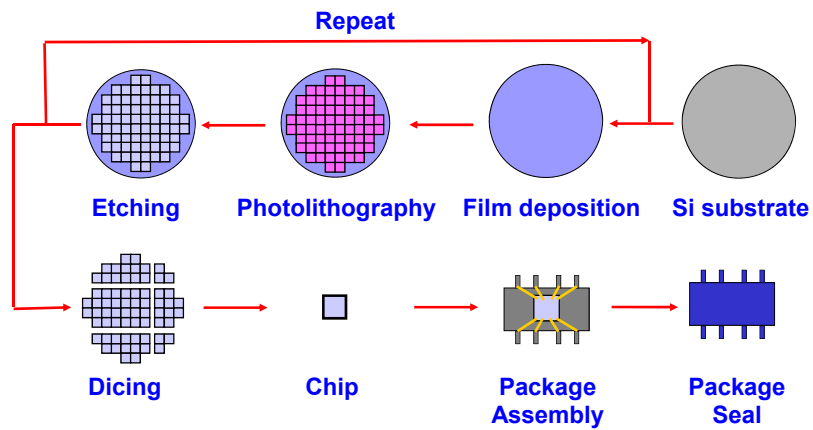
Microphone



## 課程安排



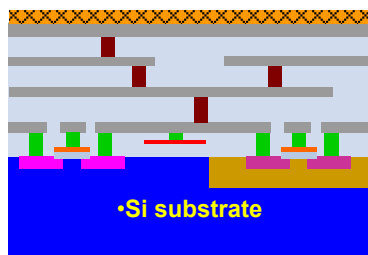
## Semiconductor processes



## Standard CMOS Processes

- Available in CMOS foundries: TSMC, UMC, etc...

0.35 $\mu\text{m}$  2P4M CMOS process



0.18 $\mu\text{m}$  1P6M CMOS process

